Please add the following new claim 29:

29. {NEW} A semiconductor device fabricating method as claimed in claim 26,

wherein

the ferroelectric thin film is made of a material expressed by:

 $Bi_2A_{m-1}B_m \phi_{3m+3}$ 

where A represents one selected from a group consisting of Na, K, Pb, Ca, Sr, Ba and Bi, B represents one selected from a group consisting of Fe, Ti, Nb, Ta, W and Mo, and m represents a natural number.

## **REMARKS**

The above amendments are made to place the claims in a more traditional format.

Attached hereto is a marked-up version of the changes made to the claims by the current amendment. The attached page is captioned "<u>Version With Markings To Show</u>

<u>Changes Made</u>."

By:

Respectfully submitted,

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